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(54) Title: ADVANTAGEOUS RECORDING MEDIA FOR HOLOGRAPHIC APPLICATIONS

(57) Abstract: High performance media suitable for recording with a blue laser is disclosed. The blue-sensitized holographic media provides greater dynamic range and higher sensitivity than previously disclosed blue-sensitized holographic media. These media can be used for diverse applications such as data storage where the articles provide denser data storage and more rapid hologram writing times or for optical waveguides where the articles provide greater optical confinement and more rapid manufacturing times.

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